

ABSTRACT OF THE DISCLOSURE

To provide a film forming apparatus in which an impurity contained in an organic compound is separated to be removed and a film is formed without decreasing the purity of the purified organic compound, whereby a high-purity organic compound is formed. A
5 film forming apparatus of the present invention includes a purifying chamber for purifying an organic compound and a film forming chamber for vapor-depositing the purified organic compound onto a substrate. The organic compound purified by a zone melting method in the purifying chamber can be vapor-deposited onto the substrate provided in the film forming chamber without decreasing the purity thereof, so that a high-purity organic
10 compound layer can be formed.